

## **BSETEQ NT1 Plasma Cleaner / Etch System**

**Supplier: BESTEQ**

**Model: NT1**

### **Description**

The NT series comes with a state of the art 13.56 MHz RF generator with power ranging from 0-600 watts.

### **Features:**

To control the major characteristics of the etching process, such as:

- Etch Rate
- Selectivity
- Anisotropy
- Uniformity

And other aspects of the etching process that can be manipulated, including:

- Temperature of the plasma.
- Ion Content of the plasma.
- Process completion speed.

The operator is given the ability to alter the following parameters:

- Electrode configuration
- Vacuum chamber process threshold pressure level.
- Process gas (or gases) selected for use.
- Amount of flow of selected gas (or gases).
- Amount of RF energy applied to the vacuum chamber.
- Amount of time object to be etched is exposed to the plasma.

Picture of the Equipment

